



SWTEST

PROBE TODAY, FOR TOMORROW

2022 CONFERENCE

Methodology to improve WAT probe card Probe Mark and Lifetime



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Introduction / Background

- Introduction what's ET structure
 - WAT (Wafer Acceptance Test), also known as ET (Electrical Test) is an important step prior to wafers shipment from foundry to their customers. The tests include process control monitors such as diodes, transistors and resistors that are situated at the wafer scribe lines (die saw region). Normally, 9-17 sites per wafer are being tested.
- Pad size reduce trend → Reference: >100nm:~80um, ~65nm:~50um, <55nm:<~40um
- CPC is more cost-effective solution vs VPC

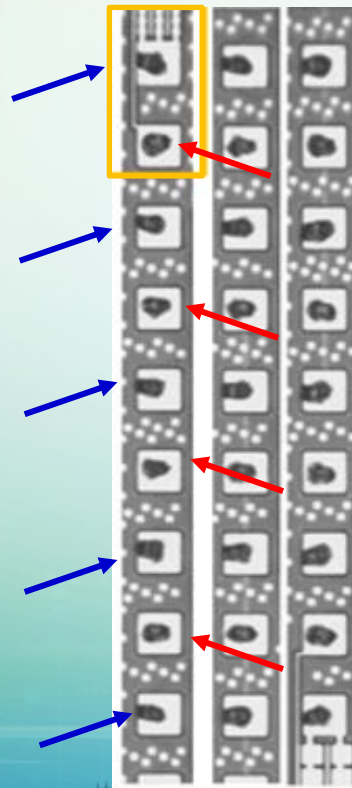
| | CPC | VPC |
|------------------------|------------------|------------------------|
| Min Pitch | 50um | 50um |
| Min Pad Size | 50 x 50um | 25 x 25um |
| Lifetime | CPC touchdown | 2* CPC touchdown |
| Cost | CPC Cost | 3* CPC Cost |
| Cost per 1M Touch down | CPC Cost/1Mil TD | 1.5 * CPC Cost/1Mil TD |

Objectives / Goals

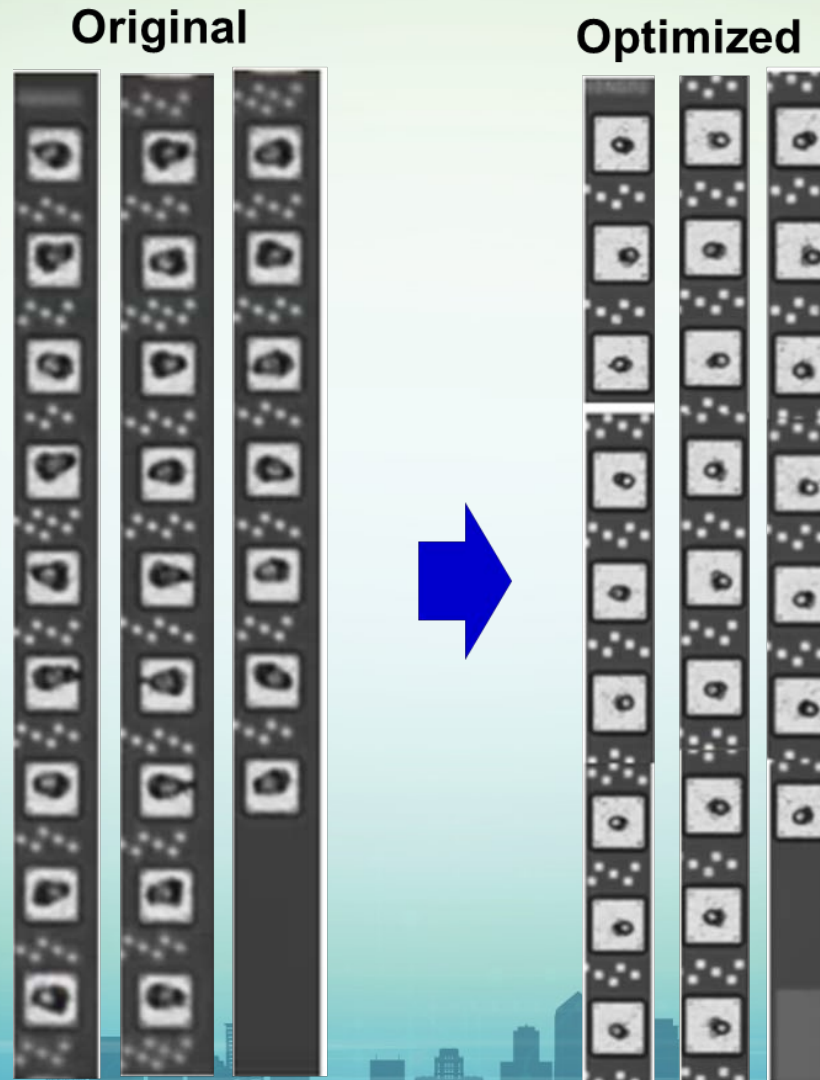
- Goal: Optimize current CPC solution to fulfill probing requirement of advanced technology nodes
 - Pad size requirement
 - Test pad size 36 x 36um which current CPC solution
 - probe margin requirement < 5um
- Challenges
 - Zig Zag probe mark issue
 - Smaller scrub mark
 - Longer lifetime

Challenges

- Zig Zag probe mark issue → Uneven probe mark occurs
 - Observed Odd Pins are touching edge and even pins have shorter scrub length
 - Happens on dual fan out card



Outcome after Optimization



Methods / Materials / Procedures

- Changing Needle Spec

- Bending Angle

- Usually set at 94° . together with beam angle , bending angel will affect how vertical the pin will be. When pin probing straight down to pad. The probe mark will be smaller , however there is risk to damage pin tip

- Tip Diameter

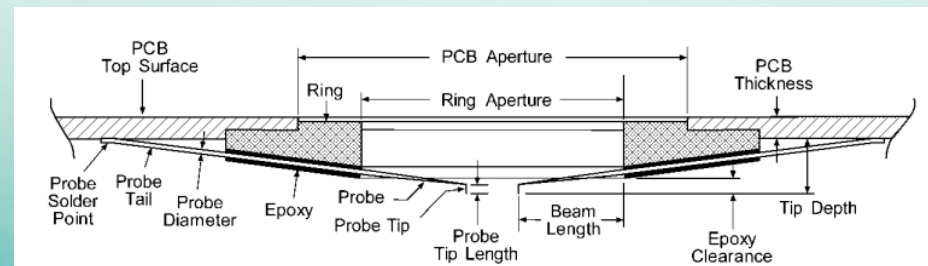
- The smaller tip diameter gives smaller probe mark , but higher risk to bend the pin tip

- A & P Offset

- Applied when needle fan-out from both side. Probe tip, instead of align in one straight line, will be adjusted towards needle body. So that when probe pin contact wafer will be slide towards the center of the pads.

- Reduce BCF (Balanced contact force)

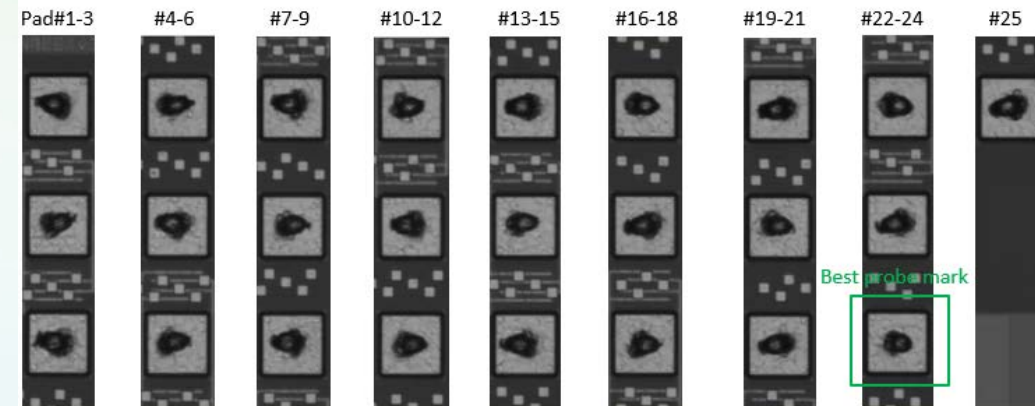
- The smaller BCF will get smaller probe mark but higher contact resistance, Reduced BCF needs to achieve balanced point which use smallest force to get solid contact and acceptable contact residence.



Summary Of Experiments

| | Original | Exp #1 | Exp #2 | Exp #3 |
|------------------|----------|----------------|----------------|----------------|
| Tip Diameter | Standard | Std - 4um | Std - 4um | Std - 4um |
| BCF | Standard | Std - 0.5g/mil | Std - 0.5g/mil | Std - 0.5g/mil |
| A&P offset | Standard | Std - 3um | Std - 3um | Std - 3um |
| Bending Angle | Standard | Standard | Std - 4° | Std - 4° |
| Bending Position | Standard | Standard | Standard | Move forward |

Original Probe Mark

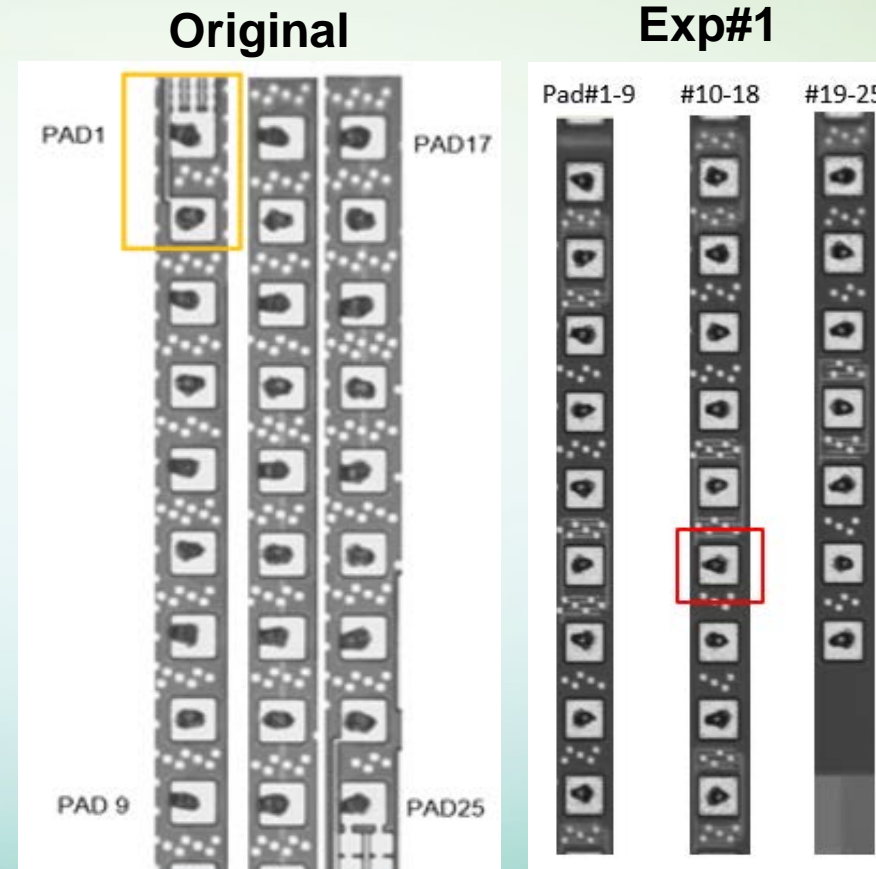


- Exp 3 can achieve small probe mark while lifetime increased to 3*N mil TD compared to N mil TD in Original

Original Vs Exp1

| | Original | Exp #1 |
|--------------|----------|----------------|
| Tip Diameter | Std | Std - 4um |
| BCF | Std | Std - 0.5g/mil |
| A&P offset | Std | Std - 3um |

- **Optimization Done**
 - Reduced tip diameter
 - Reduced BCF
 - Reduced A&P Offset
- **Exp#1 Advantage**
 - Smaller probe mark
 - More centralized

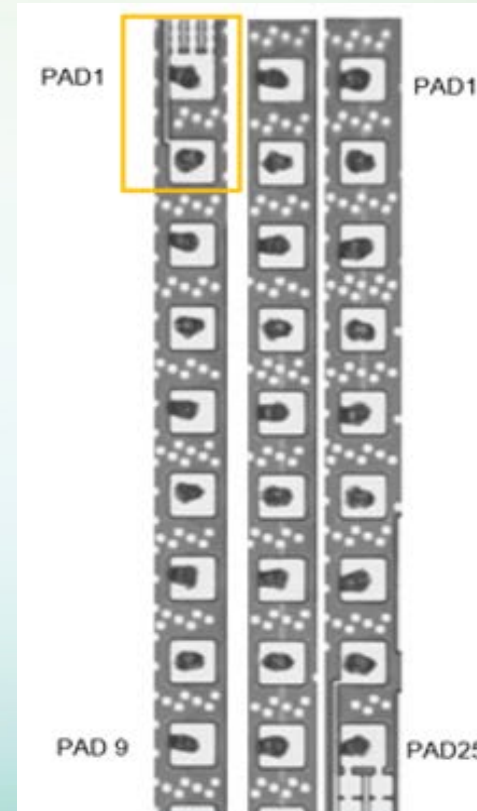


Original Vs Exp1

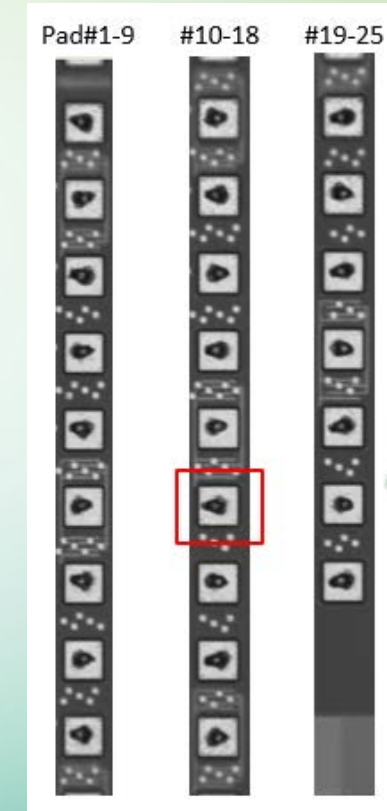
| | Original | Exp #1 |
|--------------|----------|----------------|
| Tip Diameter | Std | Std - 4um |
| BCF | Std | Std - 0.5g/mil |
| A&P offset | Std | Std - 3um |

- **Optimization Done**
 - Reduced tip diameter
 - Reduced BCF
 - Reduced A&P Offset
- **Exp#1 Advantage**
 - Smaller probe mark
 - More centralized

Original




Exp#1



Exp#1 Drawback

- Scrub Mark still can be further optimized

Original Vs Exp1 Vs Exp2

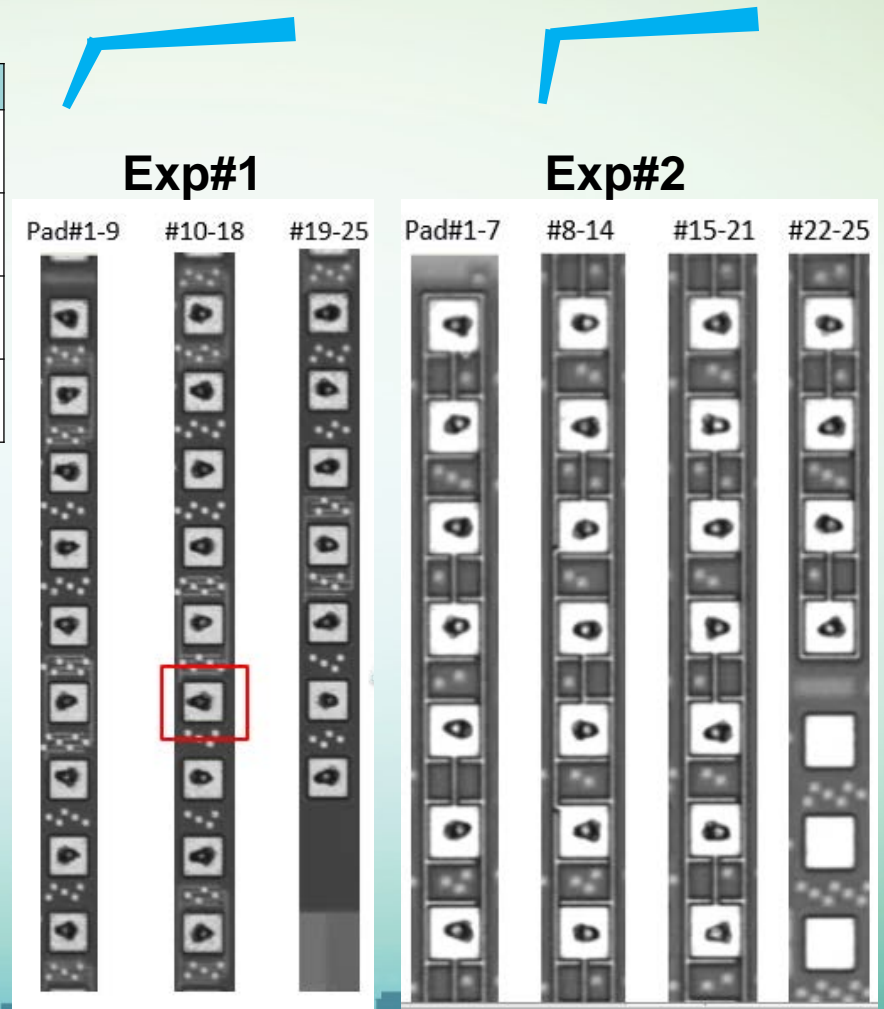
| | Original | Exp #1 | Exp#2 |
|---------------|----------|---|----------------|
| Tip Diameter | Std | Std -4um | Std - 4um |
| BCF | Std | Std - 0.5g/mil | Std - 0.5g/mil |
| A&P offset | Std | Std - 3um | Std - 3um |
| Bending Angle | Std | Std  | Std - 4° |

- **Optimization Done**

- Bending angle reduced for 100+° to 96°

- **Exp#2 Advantage**

- Smaller probe mark
- More centralized



Original Vs Exp1 Vs Exp2

| | Original | Exp #1 | Exp#2 |
|---------------|----------|---------------|----------------|
| Tip Diameter | Std | Std - 4um | Std - 4um |
| BCF | Std | Std -0.5g/mil | Std - 0.5g/mil |
| A&P offset | Std | Std - 3um | Std - 3um |
| Bending Angle | Std | Std | Std - 4° |

- **Optimization Done**

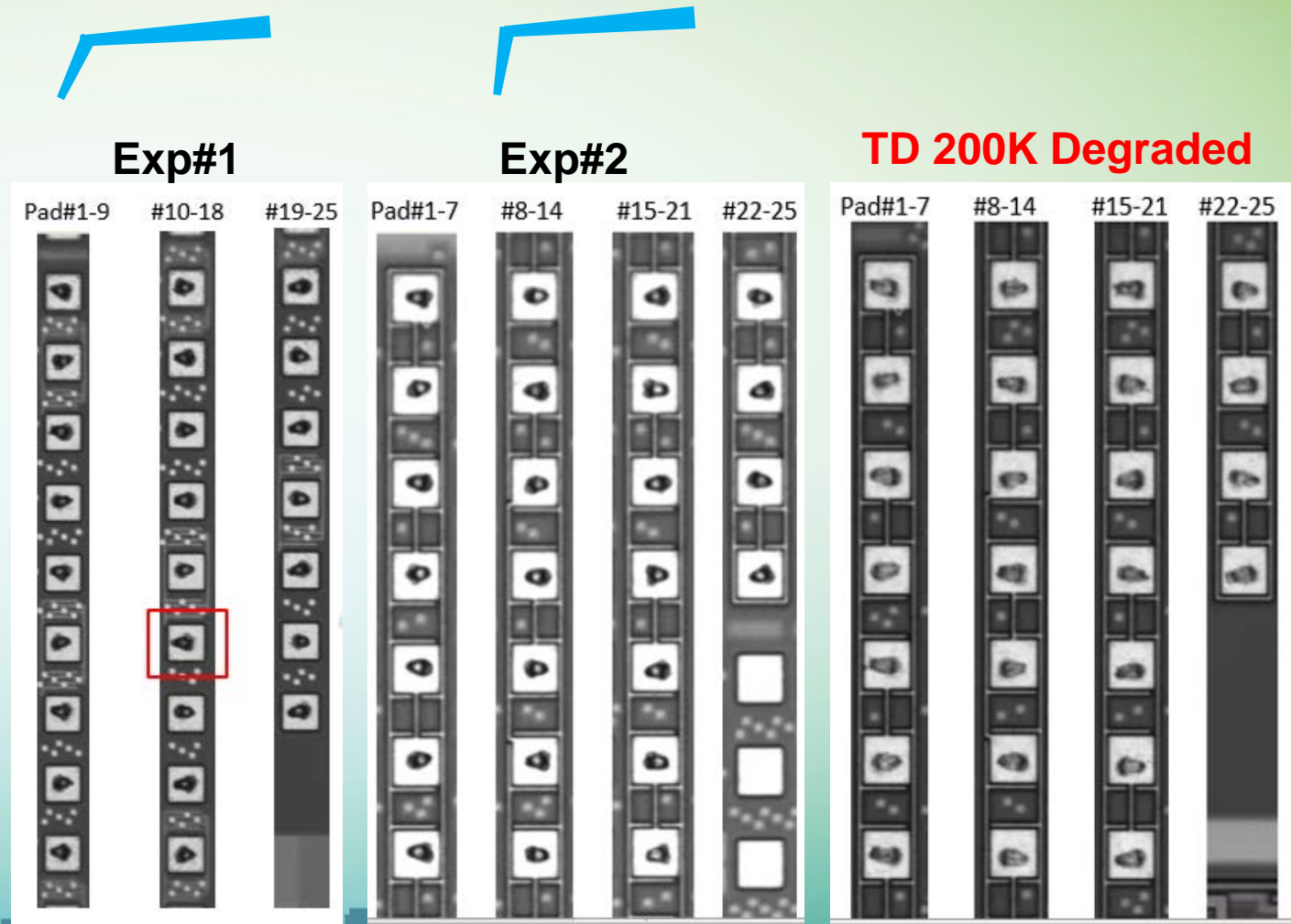
- Bending angle reduced for 100+° to 96°

- **Exp#2 Advantage**

- Smaller probe mark
- More centralized

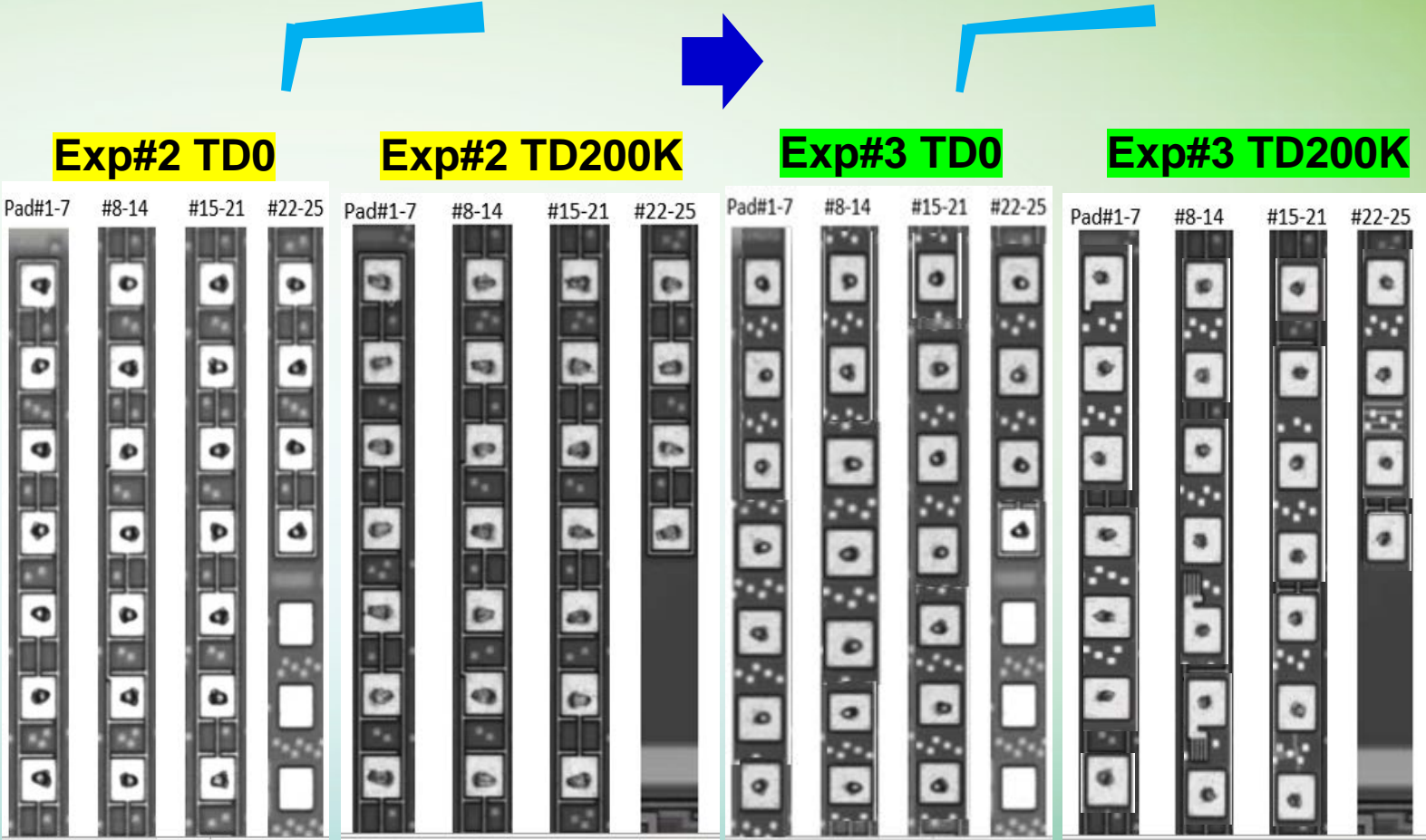
- **Exp#2 Drawback**

- Probe Mark degrade with number of TD



Exp2 vs Exp3

| | Exp #2 | Exp #3 |
|------------------|----------------|--------------|
| Tip Diameter | Std -4um | 100um |
| BCF | Std - 0.5g/mil | 3.0g/mil |
| A&P offset | Std - 3um | 12um |
| Bending Angle | Std - 4° | Std - 4° |
| Bending position | | Move Forward |



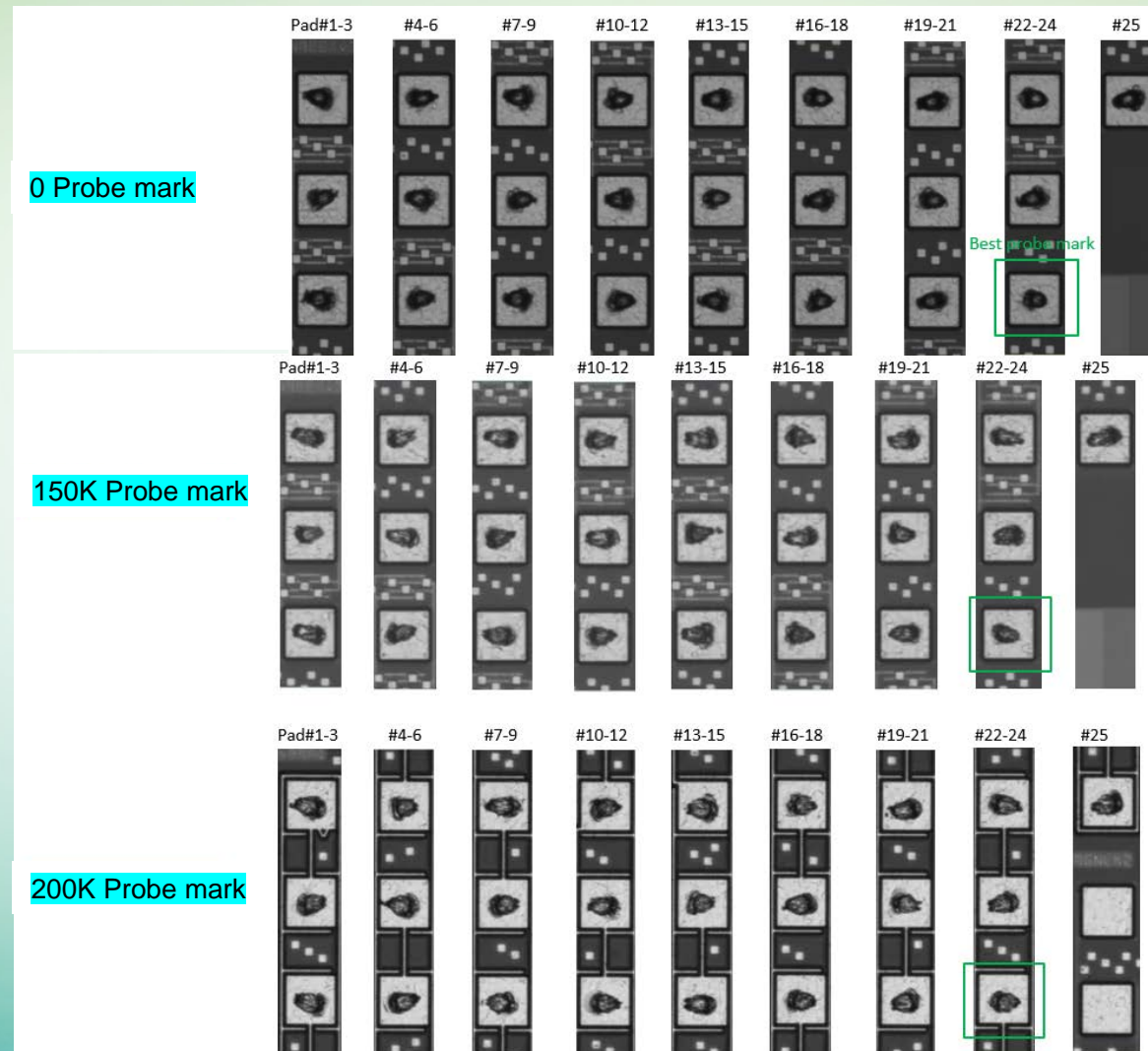
- After changing bending position, we obtained VPC alike probe mark

Optimization result summery

| | Original | Exp1 | Exp#2 | Exp#3 |
|------------------|----------|----------------|----------------|----------------|
| Tip Diameter | Standard | Std - 4um | Std - 4um | Std - 4um |
| BCF | Standard | Std - 0.5g/mil | Std - 0.5g/mil | Std - 0.5g/mil |
| A&P offset | Standard | Std - 3um | Std - 3um | Std - 3um |
| Bending Angle | Standard | Standard | Std - 4° | Std - 4° |
| Bending Position | Standard | Standard | Standard | Move forward |

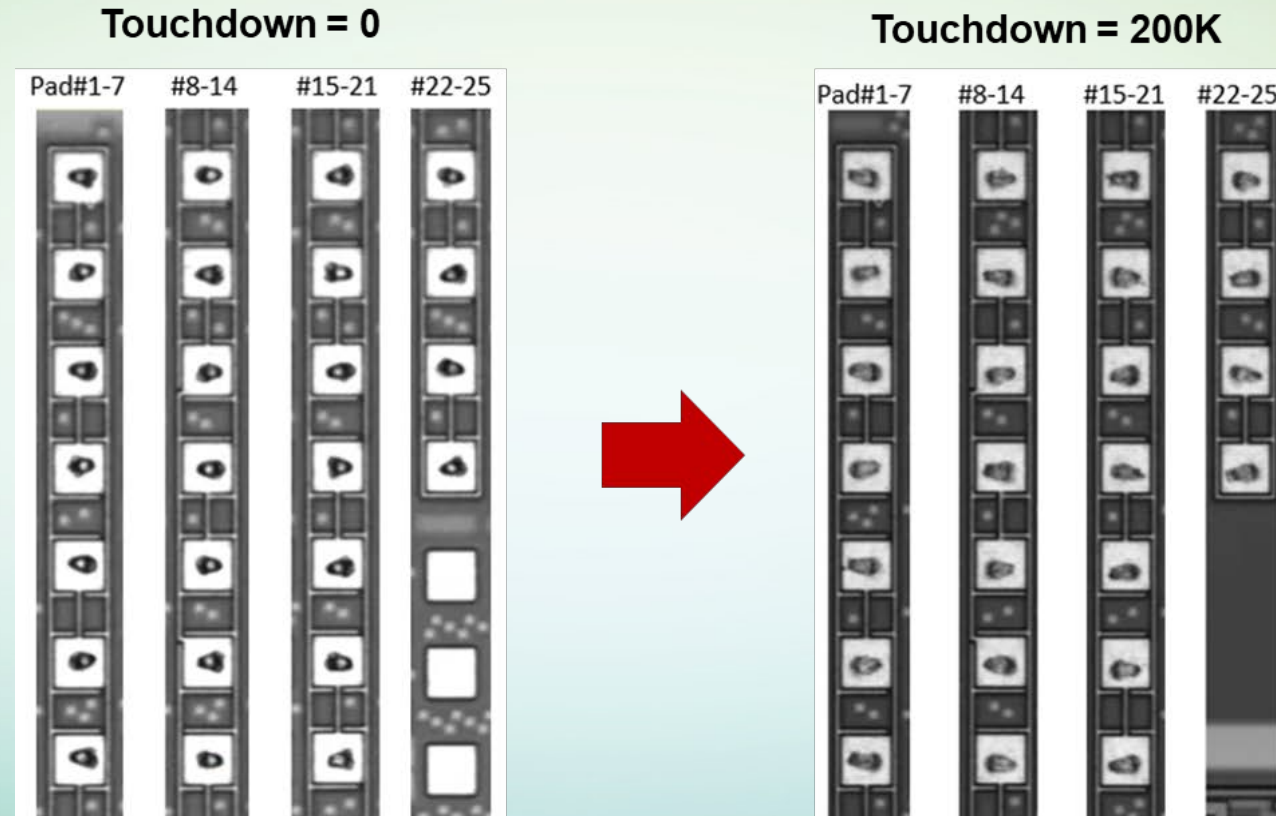
- Exp#1 shows smaller probe mark , but long scrub mark.
- Exp#2 improved scrub mark while keeping smaller probe mark, but probe mark degrades with number of touch down. Much larger probe mark at 200K touchdown
- Exp#3 much smaller probe mark and sustainable probe mark against touch down.

Probe Mark Vs touch down (Exp#1)



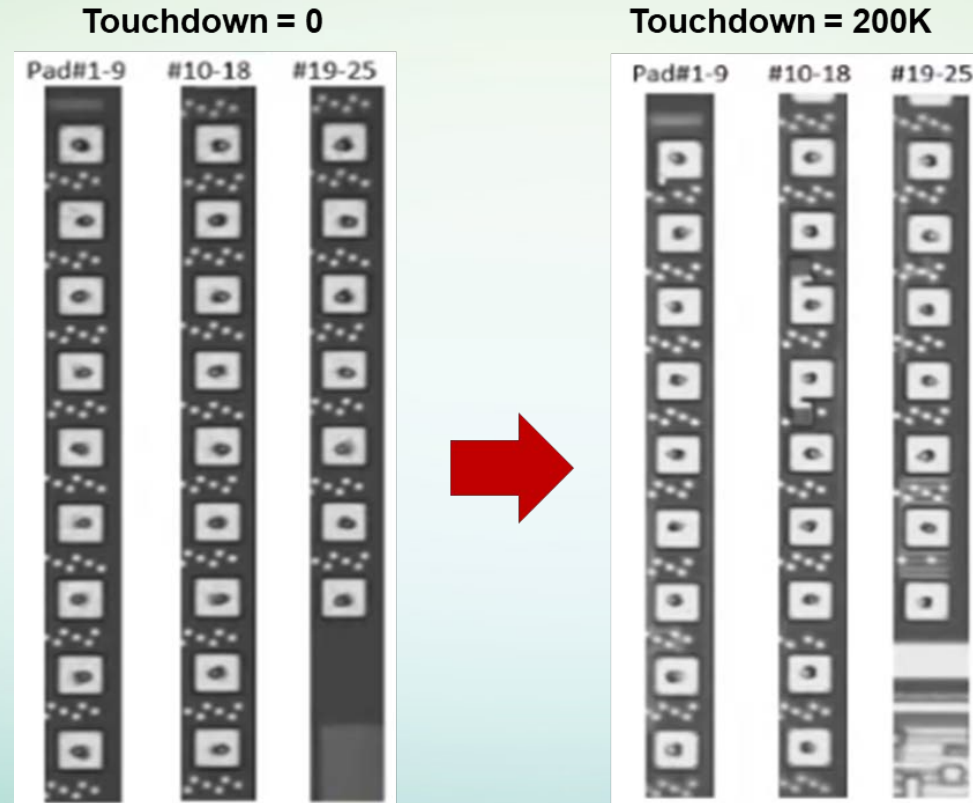
- Probe mark is getting bigger with increased number of touch down

Probe Mark Vs touch down (Exp#2)



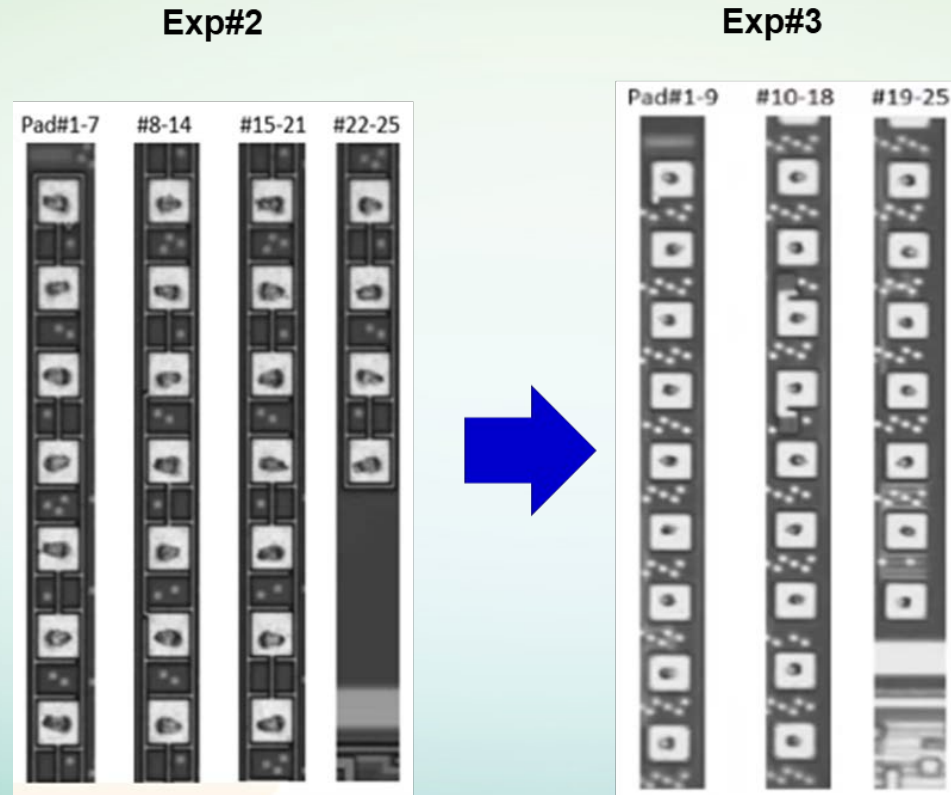
- Probe mark is ideal at 0 touch down, but degraded at 200K touchdown it's even worse than Exp#1

Probe Mark Vs touch down (Exp#3)



- With adjusted bending position probe mark perform well at 200K touchdown

Compare at 200K Touch down



- Exp#3 is greatly improved.

Lifetime comparison

| | Original | Exp#1 | Exp #2 | Exp #3 |
|------------------|----------|-----------------|-----------------|----------------|
| Tip Diameter | Standard | Std - 4um | Std - 4um | Std - 4um |
| BCF | Standard | Std - 0.5g/mil | Std - 0.5g/mil | Std - 0.5g/mil |
| A&P offset | Standard | Std - 3um | Std - 3um | Std - 3um |
| Bending Angle | Standard | Standard | Std - 4° | Std - 4° |
| Bending Position | Standard | Standard | Standard | Move forward |
| Lifetime | N Mil TD | 1.44 x N Mil TD | 1.75 x N Mil TD | 3 x N Mil TD |

- Exp#3 show better lifetime in terms number of touchdown

Summary / Conclusion

- **Summary**

- With optimization, current CPC solution can probe down to 28um x 28um pad size with 5um probe margin
- Probe mark can maintain at good shape at min 200K touchdown
- Lifetime has been improved from 3 times

- **Follow-On Work**

- Continue to monitor the probe resistance consistency, make sure probe card contact with wafer properly with increased number of touch down
- Evaluating new cleaning media to further extend the shelf-life of the probe pins is on-going.

Acknowledgement

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